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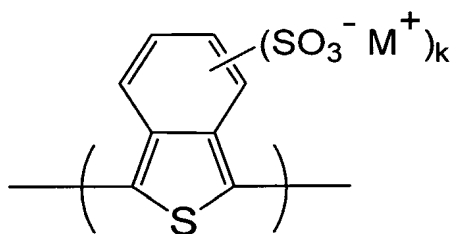
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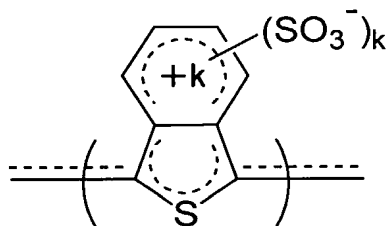
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(54) Title: POLYMER FOR ANODE BUFFER LAYER, COATING SOLUTION FOR ANODE BUFFER LAYER, AND OR-  
GANIC LIGHT EMITTING DEVICE



( 1 )



( 2 )

(57) Abstract: The present invention relates to:  
a polymer for an anode buffer layer in an organic  
light emitting device comprising a self-doping  
conductive polymer having a pH value of 3 to 7  
in a 1% by mass aqueous solution, the polymer  
containing monomer unit (s) represented by  
the following formula (1) and/or (2) wherein M<sup>+</sup>  
represents a hydrogen ion, an alkali metal ion,  
or a quaternary ammonium ion, k represents 1  
or 2, +k represents a positive charge number,  
and a hydrogen atom in the aromatic ring may  
be replaced by a substituent, an anode buffer  
layer coating solution comprising the polymer,  
and an organic light emitting device comprising  
an anode buffer layer using the polymer. The  
polymer of the present invention can overcome  
the problem of deterioration of light emitting  
layer due to extrinsic dopant.



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